

# ABSTRACT OF THE DISCLOSURE

A resist composition comprising:

(A) a compound capable of generating an active seed upon irradiation with one of an actinic ray and a radiation,

(B) a compound capable of reacting with the active seed generated from the compound (A) and/or performing electron transfer to generate an active seed different from the active seed generated from the compound (A), and

(C) a compound capable of performing electron transfer from the active seed generated from the compound (B) to generate an acid,

wherein supposing that the 1/2 wave of the oxidation potential of the active seed generated from the compound (B) is  $E_{pa}$  and the 1/2 wave of the reduction potential of the active seed generated from the compound (C) is  $E_{pc}$ , the relationship:  $E_{pc} - E_{pa} > 0$  is satisfied.